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***Zuverlässigkeit, Sicherheit und Lebensdauer  
von Sensornetzwerken im Mikro-Nano-Übergangsbereich***

***Bernd Michel***

***Fraunhofer MicroMaterials Center  
Berlin und Chemnitz***

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Zuverlässigkeit und  
Mikrointegration



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# Integrationstechnologien für vernetzte autonome Mikrosysteme

Prof. Dr. B. Michel

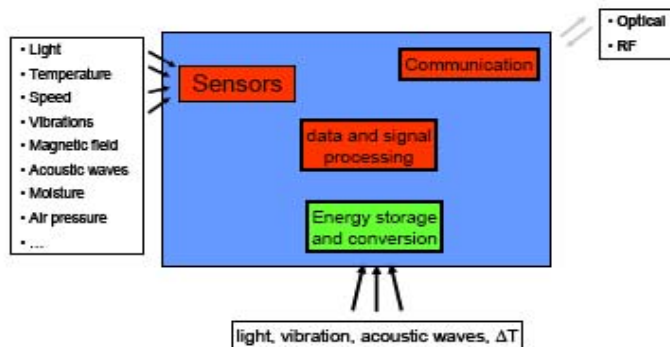
  
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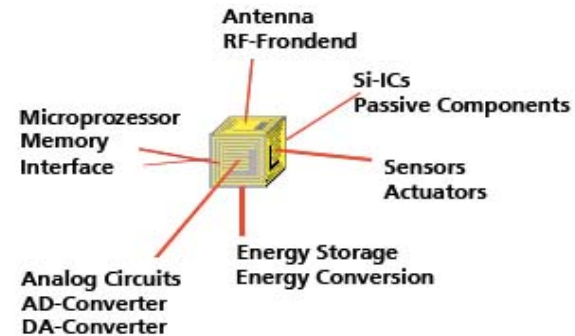
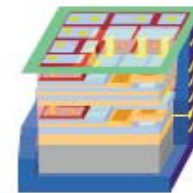
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## Self-sufficient Wireless Sensor Node

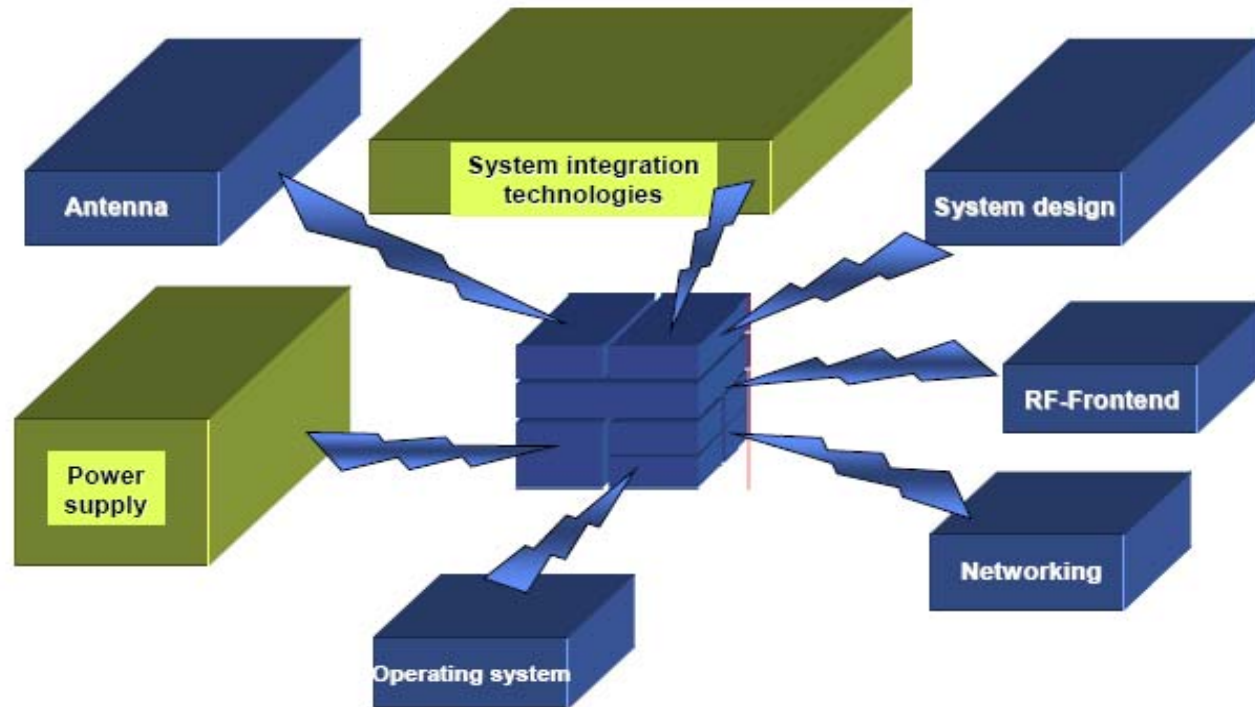
- Highly Miniaturized
- Receive, Process, Store and Send Data
- Integrated Sensors, Signal /Data Processing,
- Wireless Interface
- Power Conversion



## Vision: e-Grain



## e grain – building blocks

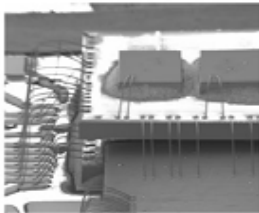
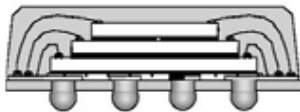


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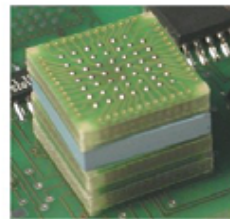
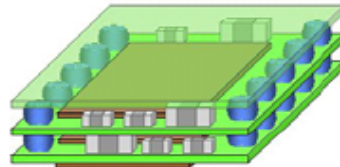


## Systembetrachtungen zur Miniaturisierung Hetero System Integration – Technologies

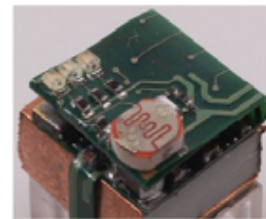
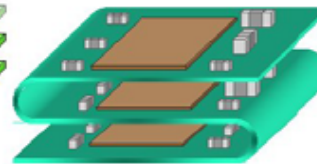
stacked  
dies



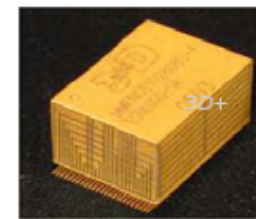
stacked  
modules



folded  
flex

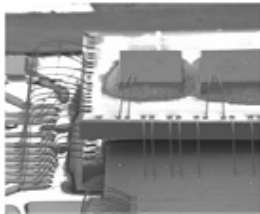
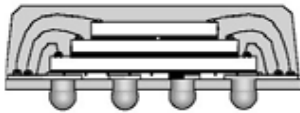


molded  
devices

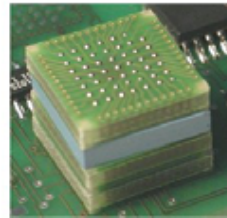
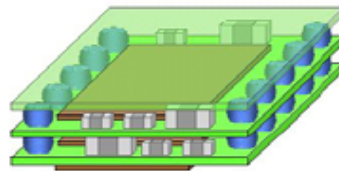


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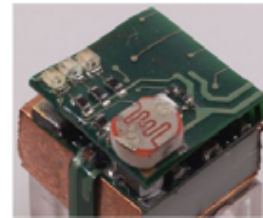
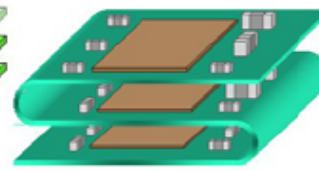
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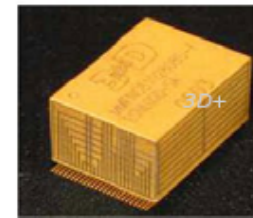
stacked  
modules





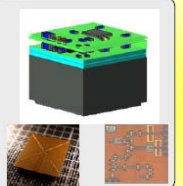
folded  
flex

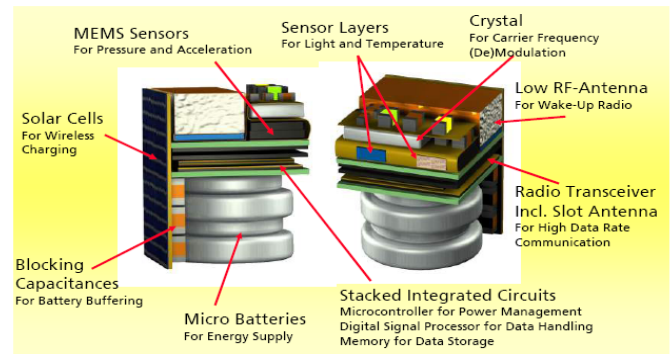


molded  
devices

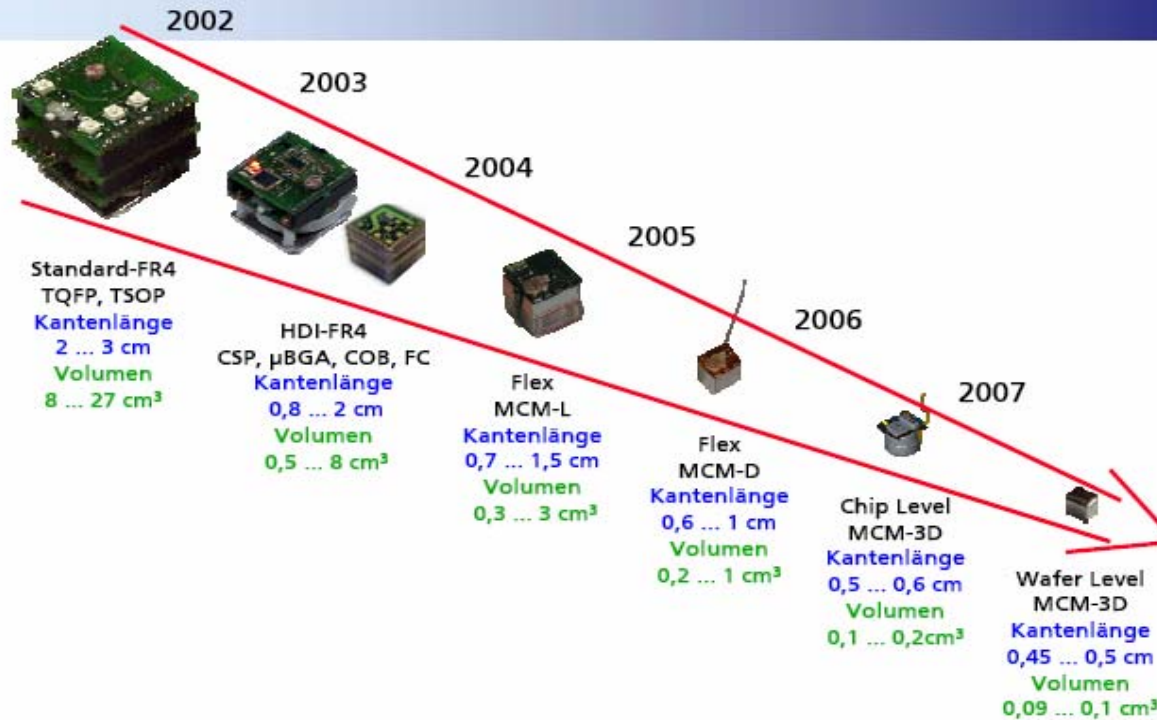


## Flex Technologies for eGrains

<p>μC: 8bit RF: 0,3 - 1GHz</p>  <p>Hohe Reichweite</p>	<p>μC: 16bit RF: 2,45GHz</p>  <p>Hoher Datendurchsatz</p>	<p>μC: 16bit RF: 24,5GHz</p>  <p>Hohes Miniaturisierungspotential</p>
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# eGrain-Roadmap



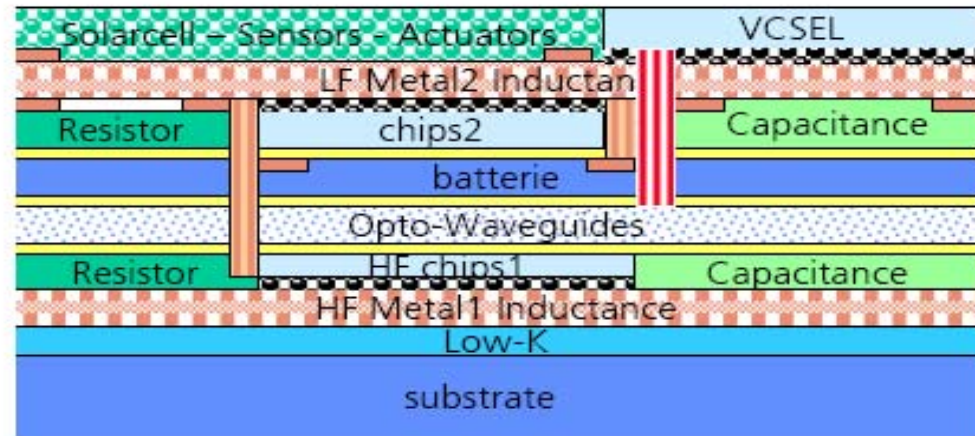
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# Multifunctional Organic Substrate Technology



Reel to Reel Processing

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## Hetero System Integration

Ir

# Smart System Integration

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**More Moore**

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## Katastrophenschutz



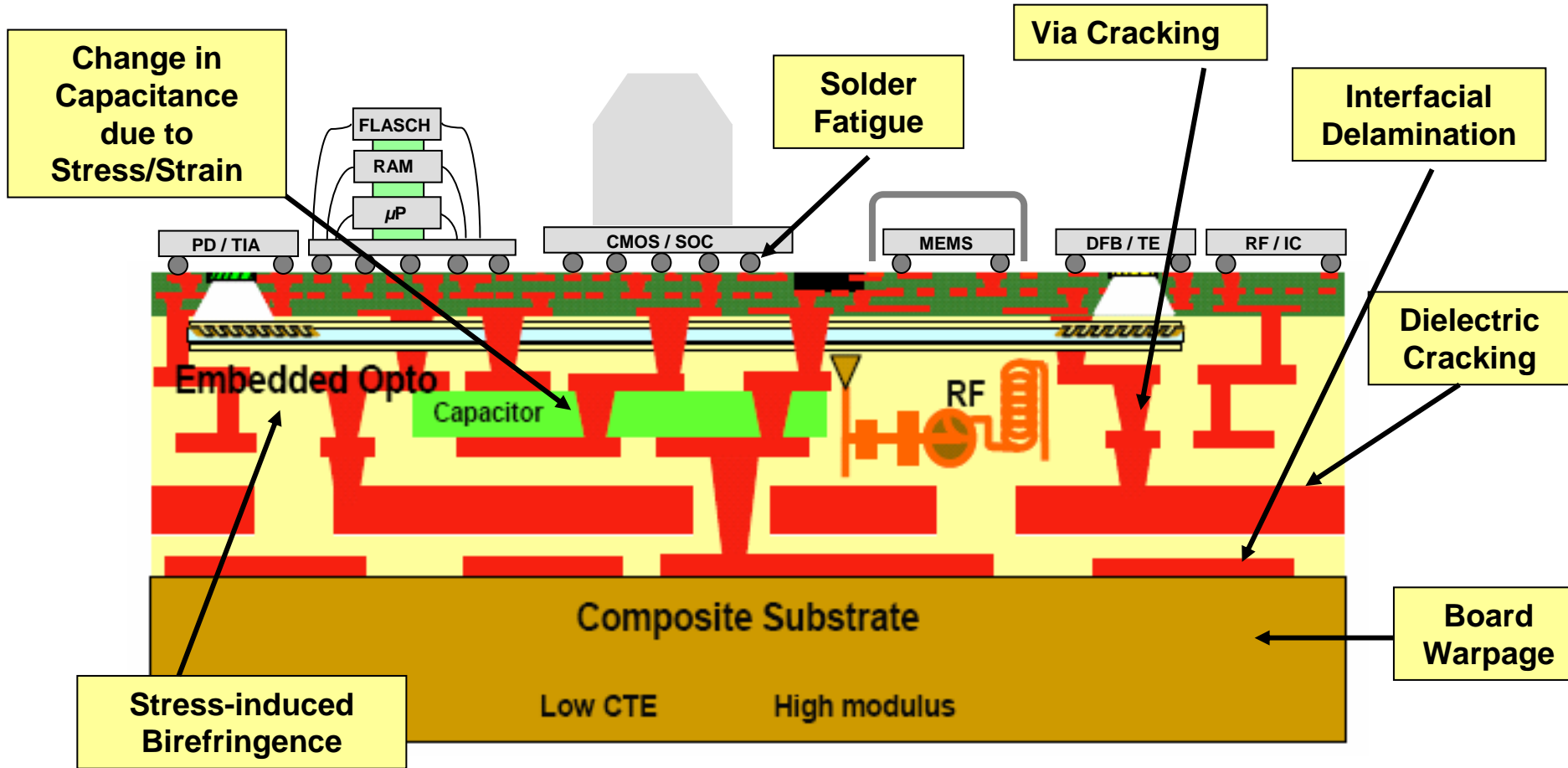
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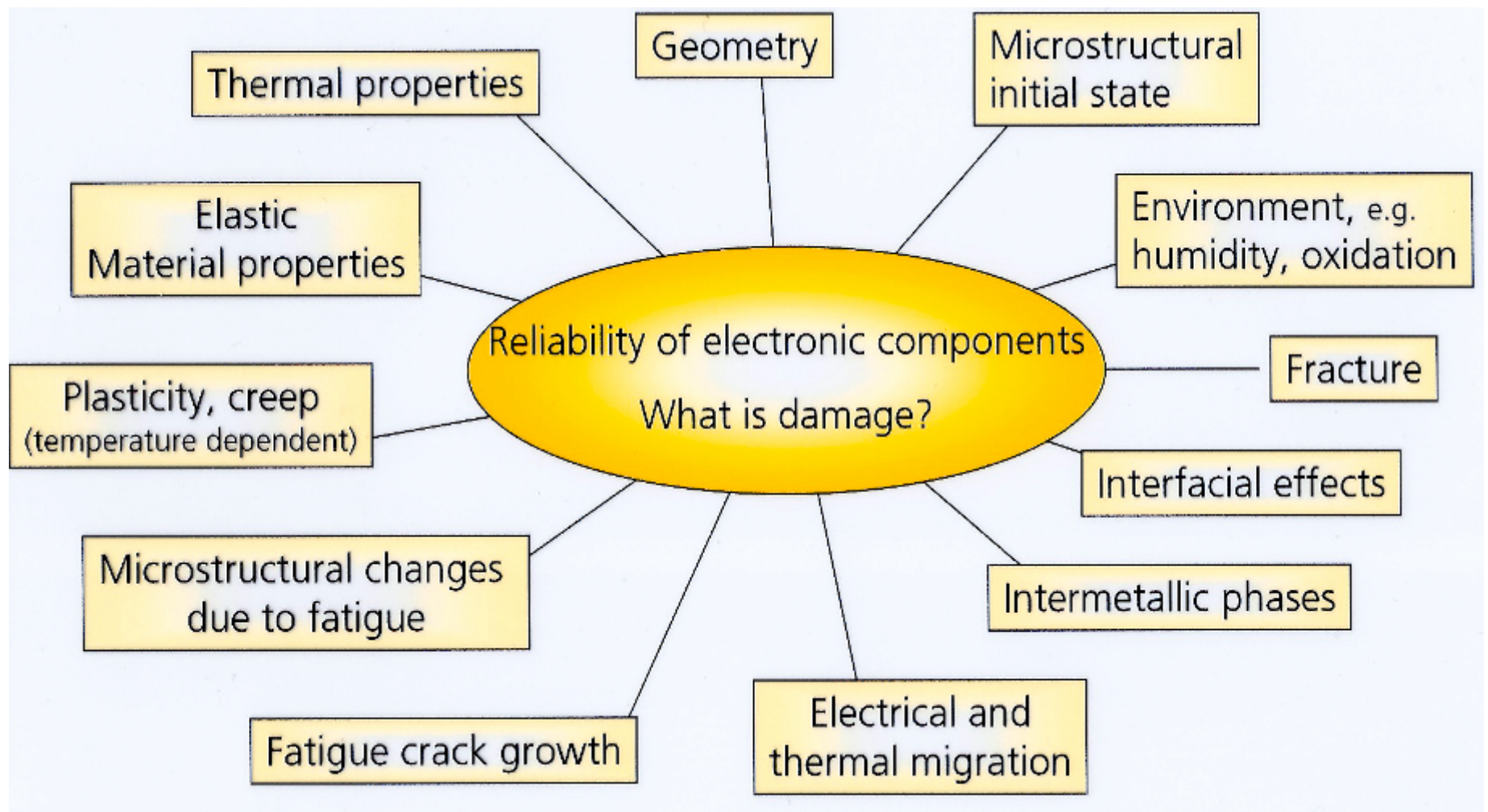
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# Potential Failure Mechanisms in SOP (System-on-Package) Microsystems

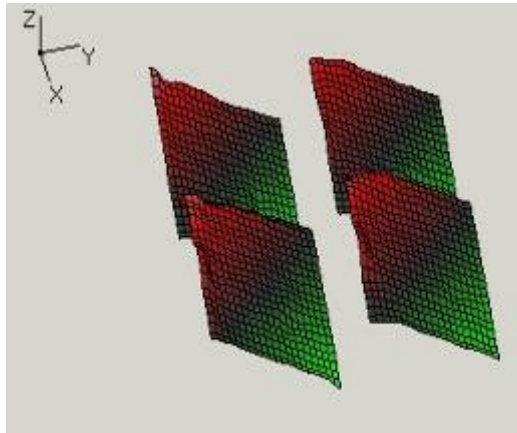


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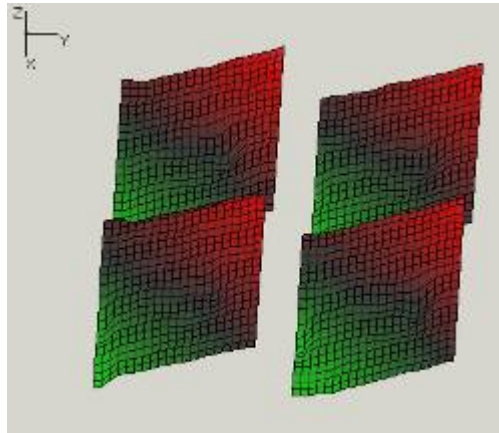




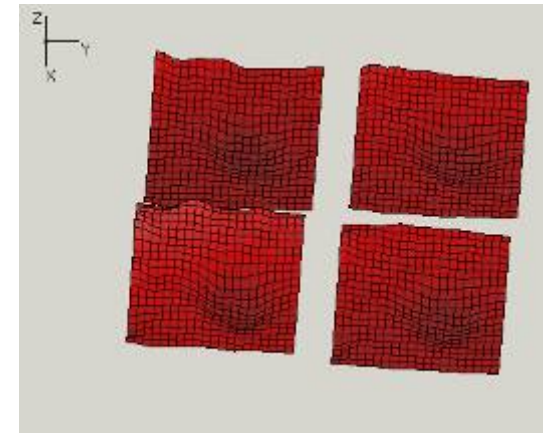
Messung



75 kHz

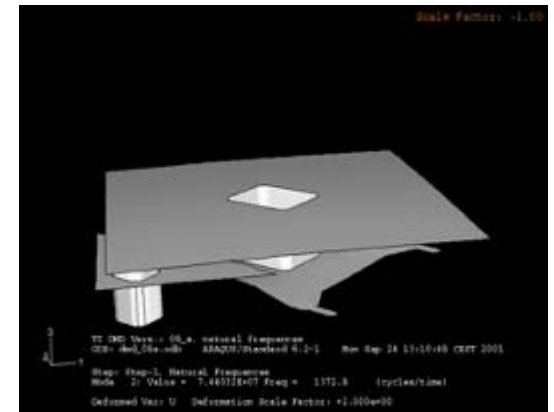
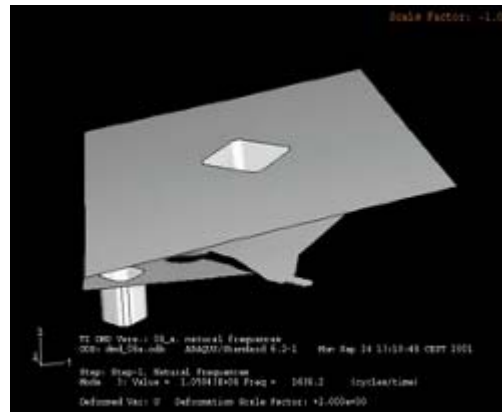
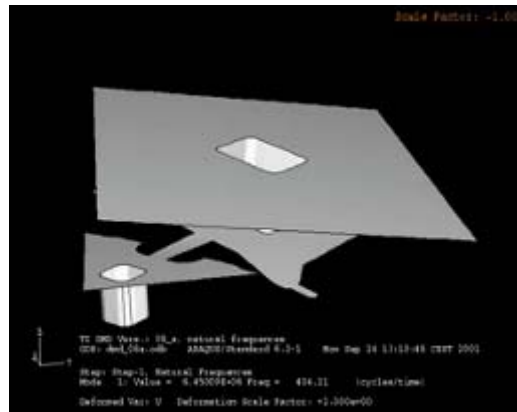


440 kHz

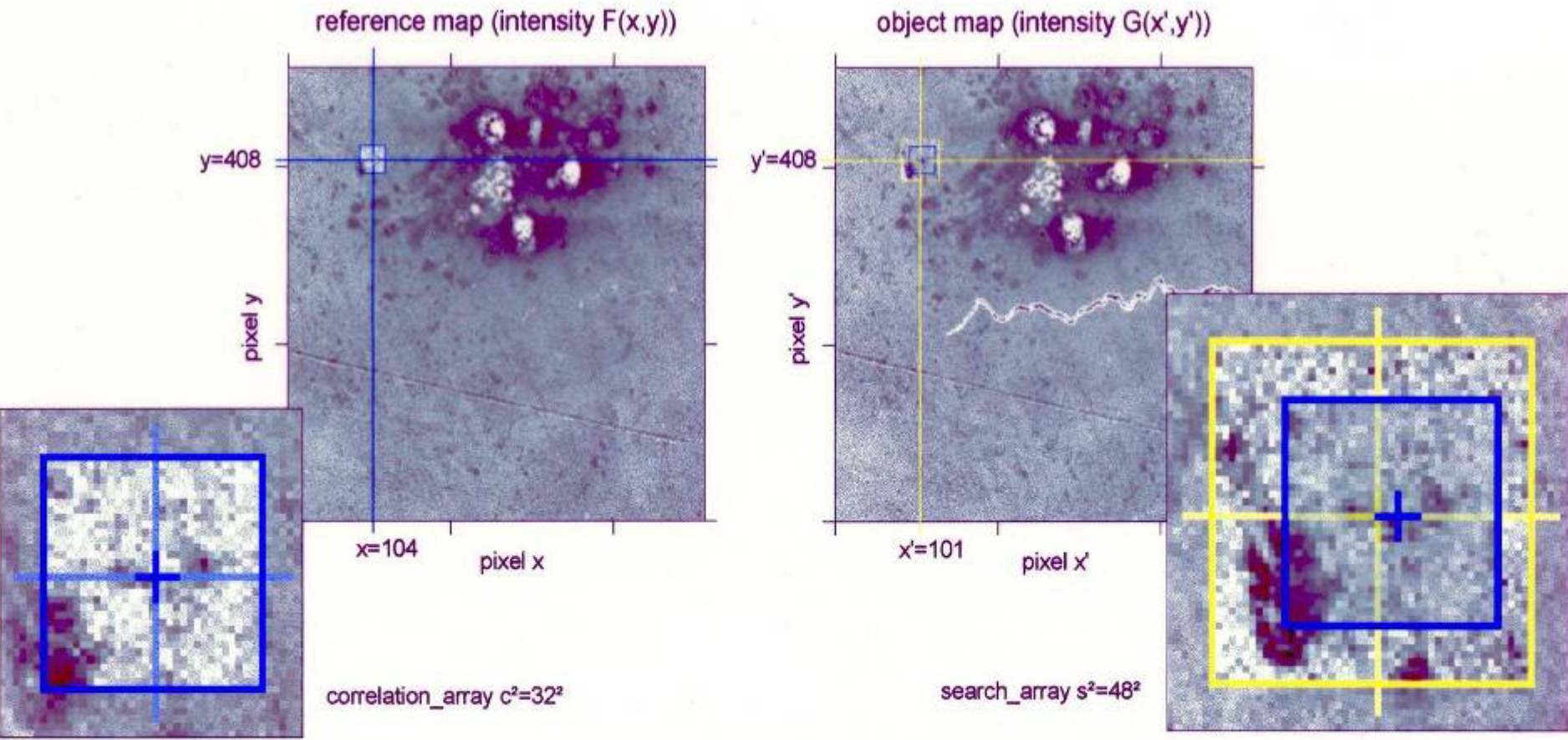


510 kHz

Berechnung



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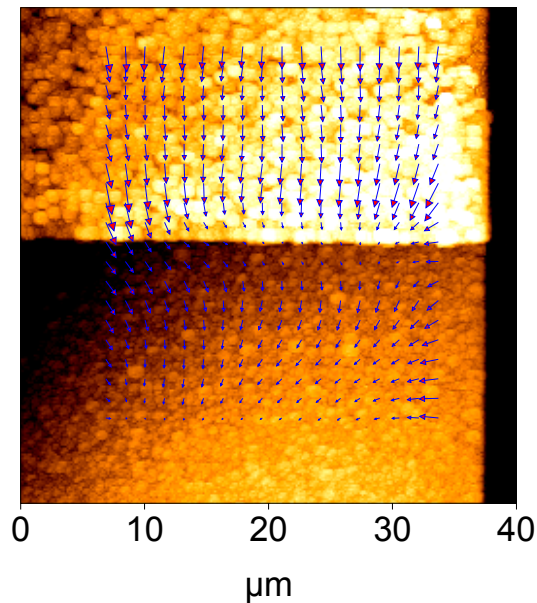


$$K(F,G) = S(F,G) / \text{sqr}[S(F)^2 S(G)^2]$$

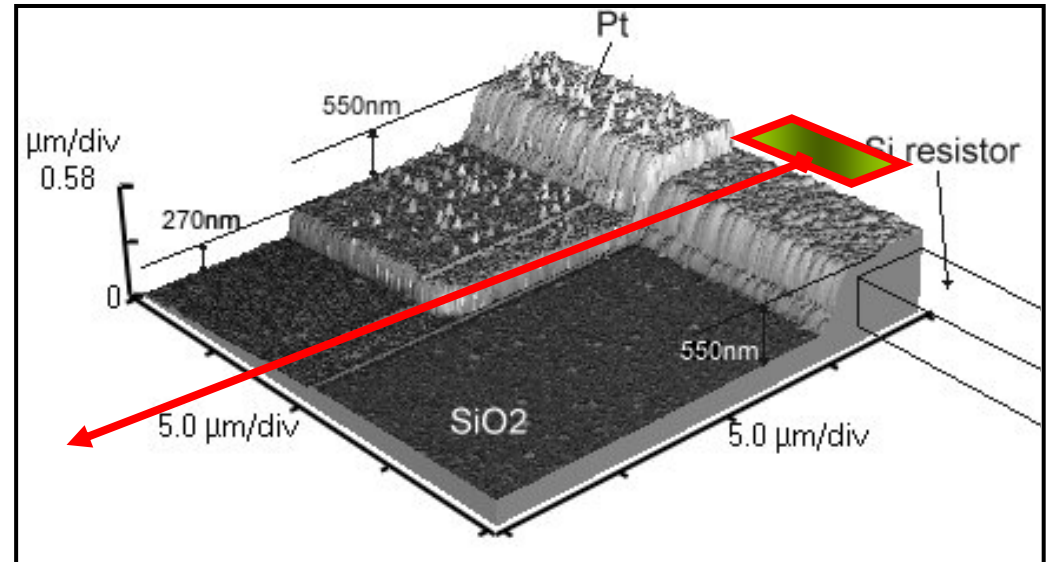
$$(u_x, u_y) = ([x'-x]+dx, [y'-y]+dy) \mid K(F,G)=\text{max}$$



# 3D Deformation Measurement on Sensor Structures by nanoDAC



local displacement [nm]



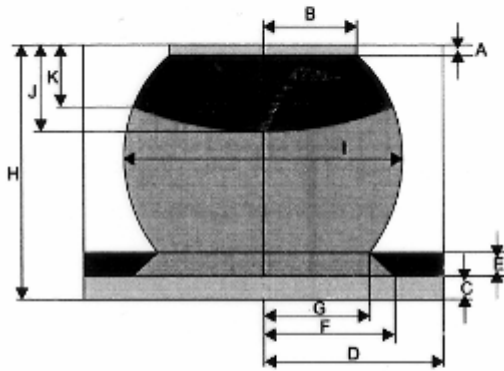
## In-plane deformation field

- sensor heating under the AFM
- temperature gap: RT – 100°C

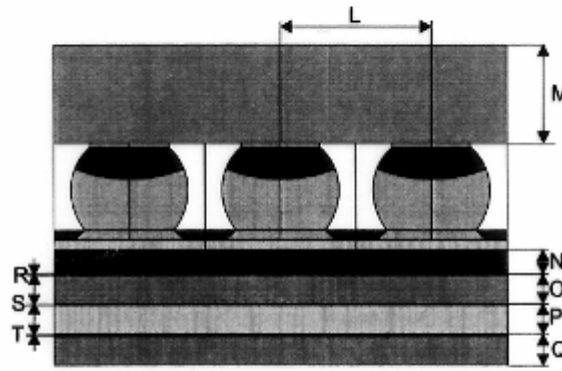
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# Parameterized FE-Model of a bump array with C4 bumps

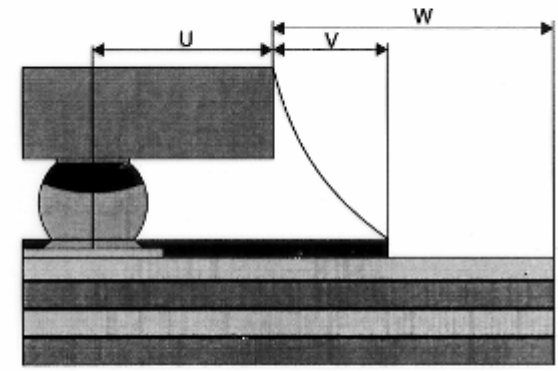
## Parameters



- A - height of the top pad
- B - radius of the top pad
- C - height of the bottom pad
- D - radius of the bottom pad
- E - height of the solder resist
- F - radius of the upper solder resist opening
- G - radius of the lower solder resist opening
- H - standoff of the whole bump
- I - largest bump radius
- J - height of the hls bump at the center
- K - height of the hls bump at the border



- L - bump pitch
- M - thickness of the die
- N - Thickness of the 1st board layer
- O - Thickness of the 2nd board layer
- P - Thickness of the 3rd board layer
- Q - Thickness of the 4th board layer
- R - Thickness of the 1st copper layer
- S - Thickness of the 2nd copper layer
- T - Thickness of the 3rd copper layer

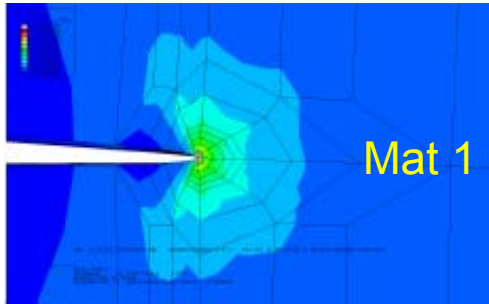


- U - distance between the die edge and the center of the outer bump row
- V - "width" of the underfill fillet
- W - distance between the die edge and the board edge

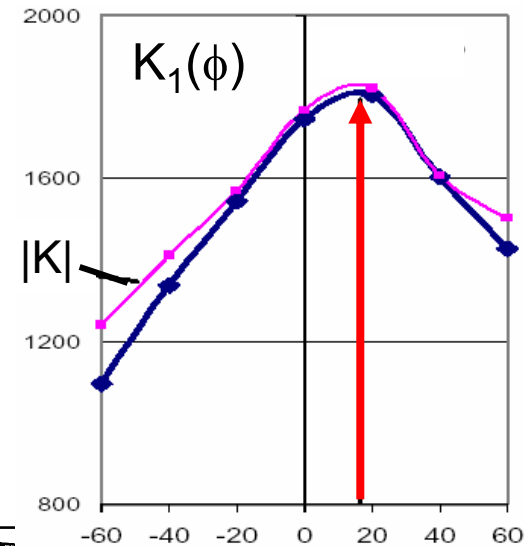
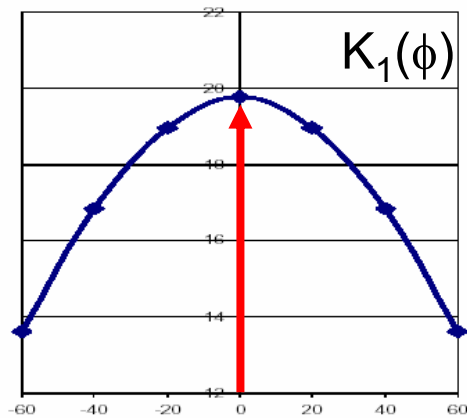
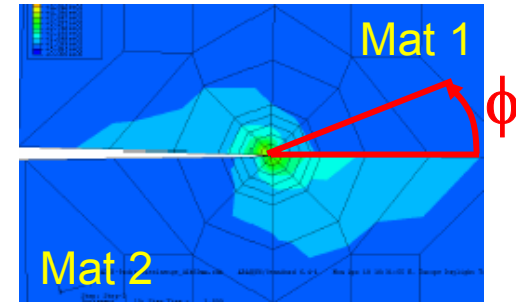
# Bruchmechanik

## Mode Mix am Interface

Riss im Bulk



Riss am Interface



→ Am Bi-Material Interface existiert immer ein Mode-Mix, d.h. Phasenwinkel  $\phi \neq 0$ , also nie eine reine Mode-I Belastung

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- 
- **Nanoreliability**
  - **Microreliability**

# Wissenschaftliche Ziele (I)

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- **Lebensdauerkonzepte für miniaturisierte Komponenten und Systeme**
  - Langzeitlebensdauer (> 15 Jahre)
  - **komplexe Belastungen** (therm., mechanisch, elektrisch,...)
  - extreme Einsatzbedingungen
  - **neue Werkstoffe in miniaturisierten Verbänden** (z. B. Biomaterialien)
  - "nano"-Applikationen
  - **Rißvermeidungsstrategien**
  - Restlebensdauerbewertung
  - high reliability applications
  
- **Entwicklung, Aufbereitung und Einsatz von Simulationsmethoden - Design für Reliability**
  
- **Schritt von der Komponentenzuverlässigkeit zur Systemzuverlässigkeit**



# Zuverlässigkeitslücke (Reliability Gap)

„Design for Reliability“

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# Bridging the gap between Micro and Nano

Coupling FE & Atomistic

[m]

$10^{-3}$

$10^{-6}$

$10^{-9}$

$10^{-12}$

“Zoom over Scale”  
over many orders of  
magnitude

“TOP-DOWN”

(a) Finite Elements:  
Continuum,  
Macroscopic

(b) Homogenisation  
FE-Modelling of Nano-  
Structure on a Macro-  
Scale: No Size Effects

Partly  
**semi-empirical**  
Methods necessary  
(Parameter-Fitting)

(c) Molecule Level  
Force-field; Mesoscopic Interaction of  
Molecules/Segments, Ab-initio based  
approximate/Effective Models

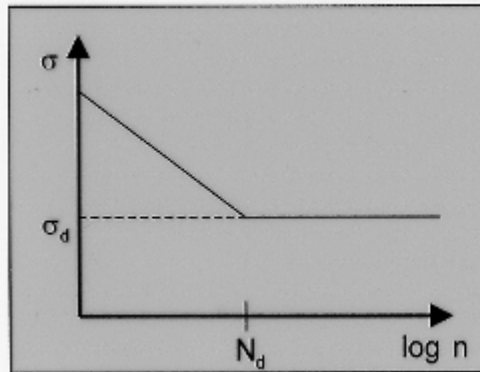
“BOTTOM-UP”

(d) Atomic-Scale:  
Ab-Initio Calculations



# High Cycle Fatigue – Life Time Prognosis – Concepts

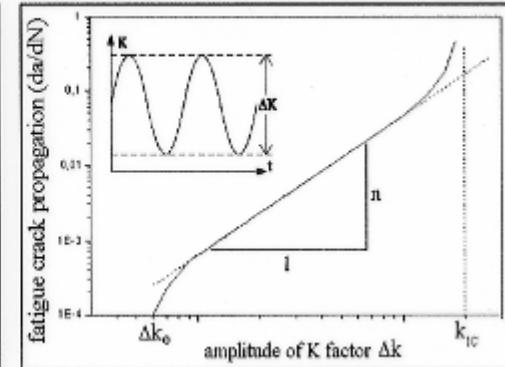
## Fatigue Curves (Wöhler et al)



## Kinetic Damage Equations

- normalized damage measure ( $D=0$  – undamaged,  $D=1$  – failure)
- Damage increment  $\frac{dD}{dn} = F[D, \sigma(n)]$

## Crack Growth - Fatigue Curves



### Modified Concepts

#### Reference Quantity:

- Strain
- Stress or strain functions

#### Changes in Fatigue Curves dependent on:

- Damage Concept
- 

#### Independent Damage Increments

$$\frac{dD}{dn} = \frac{1}{N(\sigma_i)}$$

#### Generalized Damage Concepts:

• e.g.:

$$\frac{dD}{dn} = F_1(D) \cdot F_2(\sigma(n))$$

#### Paris-Erdogan Concepts

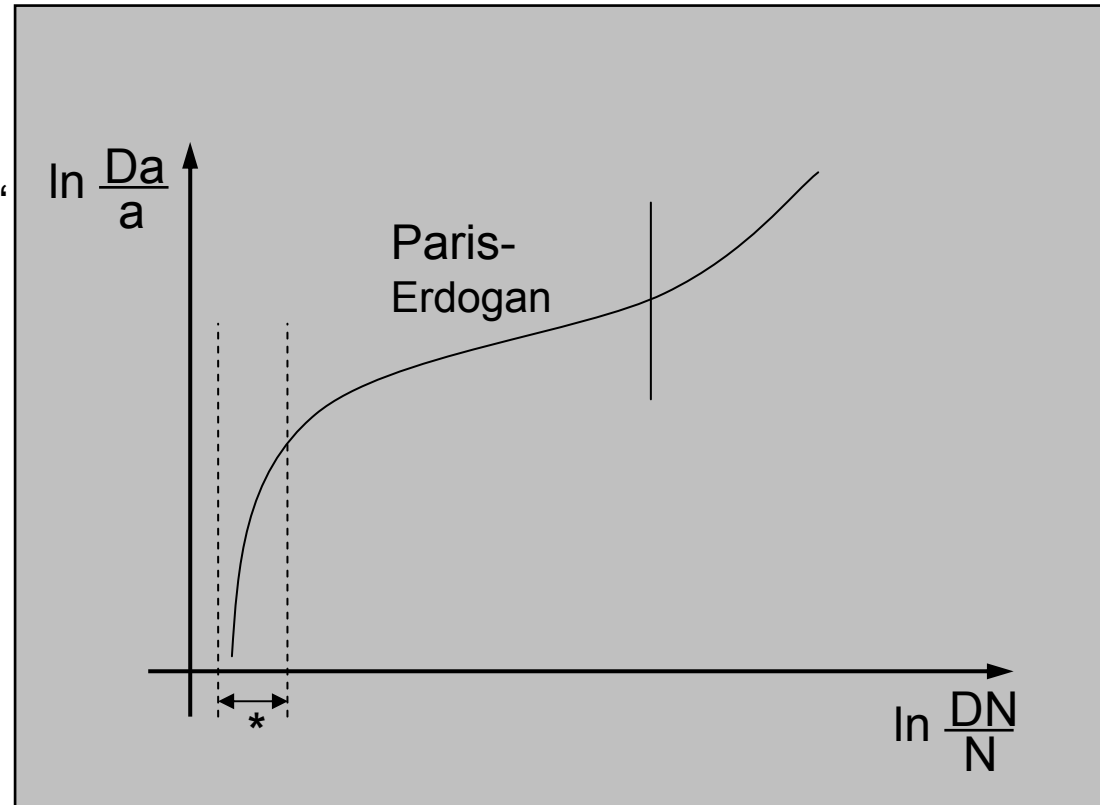
$$\frac{da}{dn} = \alpha \cdot \Delta K^N$$

#### Generalized Concepts

- Energetic approach
- Micro-mechanics
- Formalized crack fatigue concept

# Nanoreliability

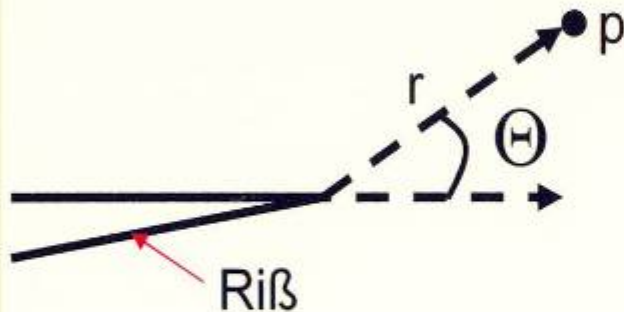
„Theory of Defects“  
„Lattice Theory“  
„Molecular Modeling“  
„Nanomaterials Simulation“



\* „nano“ – short cracks

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# Risse in Mikrosystemen in mechanischen und elektrischen Feldern



$$\sigma_{ij} = \frac{1}{\sqrt{r}} \left\{ \begin{array}{l} K_I \cdot f_{ij}^I \cdot (\Theta) + K_{II} \cdot f_{ij}^{II} \cdot (\Theta) \\ + K_{III} \cdot f_{ij}^{III} \cdot (\Theta) \\ + K_{IV} \cdot f_{ij}^{IV} \cdot (\Theta) \end{array} \right\}$$

$K_I, K_{II}, K_{III}$ : klassische Spannungsintensitätsfaktoren der Bruchmechanik  
 $K_{IV}$ : „elektrischer Beitrag“ zum mechanischen Spannungsfeld

# ***European Center for Micro- and Nanoreliability***

## **Äufgaben:**

1. Bildung von ***Eurolabs***
2. Schaffung eines ***European Networks*** der Eurolabs  
Executive Board, Scientific Advisory Board,  
Industrial Board, Board of Directors etc.
3. Awards, Expertisen
4. National Contact Points zur Zuverlassigkeitskompetenz
5. Konzeption, Initiierung und Koordinierung und von Projekten
  1. EU: IP, CRAFT, COST...
  2. International (z.B. USA-Deutschl....)
  3. National (BmbF, AIF, DFG, ...)
  4. Regional (Land...)

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Dept. Mechanical Reliability  
and Micro Materials



# *Micronanoeliability 2007*

1st International Conference

## **Microreliability and Nanoreliability in Key Technology Applications**

*Berlin, Sept. 2-5, 2007*

*Hotel Courtyard by Marriott Berlin*

*[www.micronanoreliability2007.com](http://www.micronanoreliability2007.com)*

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